Total Control	-		 	
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MANIPAL UNIVERSITY, MANIPAL III SEMESTER M.Sc. PHYSICS SUBJECT: CONDENSED MATTER PHYSICS I - PHY 707.1 Parepared 649 (MAKE UP EXAMINATION – DECEMBER 2016) (REVISED CREDIT SYSTEM)

Fime 3 Hrs.]	[Max. M	larks: 50
Note: ☞	Answer ANY FIVE FULL questions in a continuous sequence.	
IA. Explain the	following deposition techniques (a) resistive heating (b) Flash evaporation	[5]
1B. What is glo	w discharge sputtering? Explain the operation of a glow discharge sputtering	[5]
2A. Explain the	interference method of finding the thickness of the thin films.	[5]
coating. If a	ystal with a resonant frequency of 6 MHz is used to monitor the thickness of alumin frequency shift of 0.80 kHz is observed for a particular thickness of the film, calcuthe coated layer. Density of Al is 2.7 g/cc. Constant of the crystal is 8MHz.m ² /Kg	data tha
2C. Explain the	Langmuir-Blodgett (LB) films.	[3]
3A. Explain cap	illarity theory of heterogeneous nucleation and show that $\Delta G = \frac{16\pi\gamma^3}{3\Delta G_v^2} \left\{ \frac{2-3\cos\theta+\cos\theta}{4} \right\}$	(s ³ 0)
3B. What are th	general steps involved in nucleation and growth of thin films.	[6] [4]
4A. What are di tunneling an	scontinuous thin films? Explain electron transfer between the discontinuous metal d derive an expression for electrical conductivity.	islands by
4B. Explain cor	duction mechanism in thin insulating films.	[4]
5. Assuming a transmittance	single, homogeneous and non absorbing thin film, derive an expression and reflectance of the thin film in air.	
6A. What are na	nomaterials? Classify them as per the dimensions. Give few examples.	[4]
6B. Explain any	one bottom up and top down approach for creating the nanomaterials	[6]